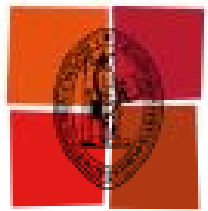


Nanodroplet deposition and manipulation with an AFM tip



Université
de Toulouse

Laure Fabié, Hugo Durou, Thierry Ondarçuhu

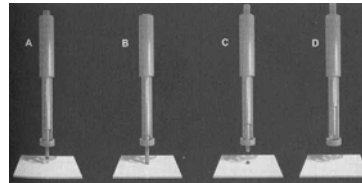
Nanosciences Group, CEMES-CNRS Toulouse (France)



Direct deposition methods

Liquid lithography

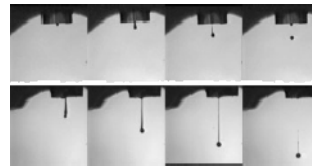
Pin and Ring method (DNA chips)



~ 200 μm

Ink jet

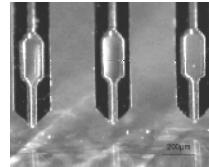
De Gan et al., *Adv Mat* 2004



10 μm

Pins

Belaubre et al., *APL* 2003

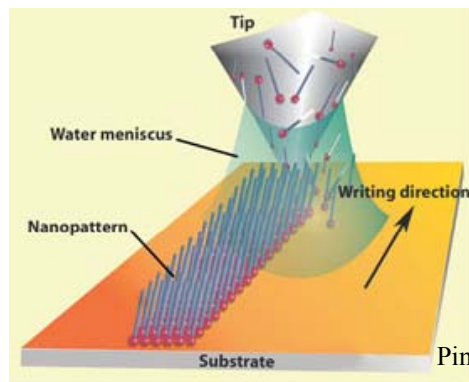


Few μm

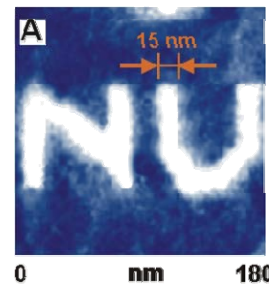
+ flexibility

-- $\text{\O} \sim 5$ to 200 μm

Dip pen lithography



Piner et al., *Science* 1999



+ $\text{\O} \sim 10$ nm

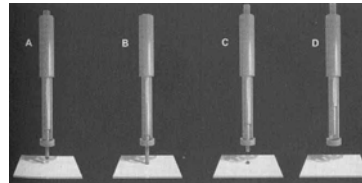
-- limited in terms of transferrable molecules

-- no reservoir

Direct deposition methods

Liquid lithography

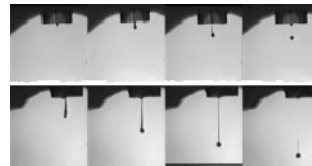
Pin and Ring method (DNA chips)



~ 200 μm

Ink jet

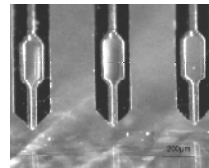
De Gan et al., *Adv Mat* 2004



10 μm

Pins

Belaubre et al., *APL* 2003

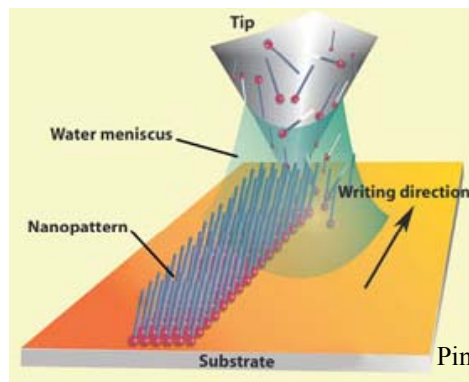


Few μm

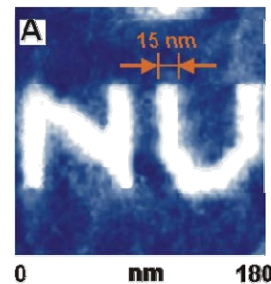
+ flexibility

-- $\text{\O} \sim 5$ to 200 μm

Dip pen lithography



Piner et al., *Science* 1999

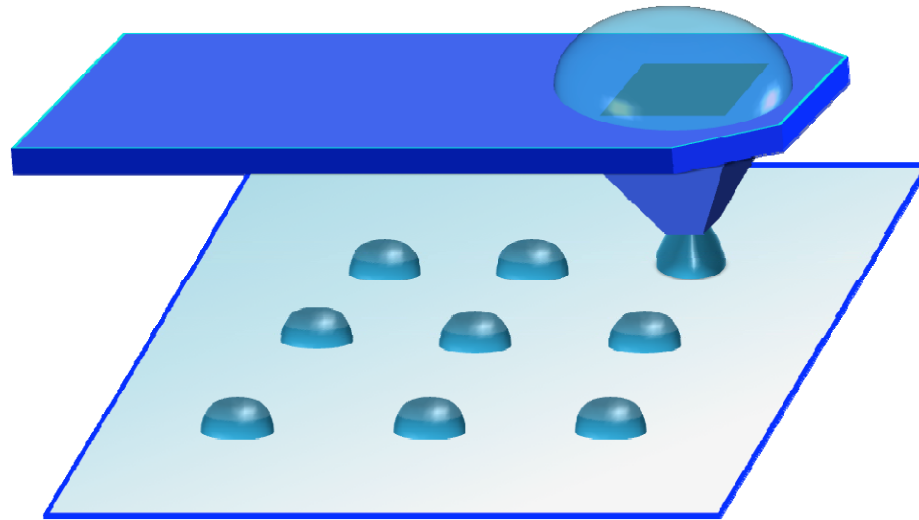


+ $\text{\O} \sim 10$ nm

-- limited in terms of transferrable molecules

-- no reservoir

NADIS : Liquid NAnoDISpensing



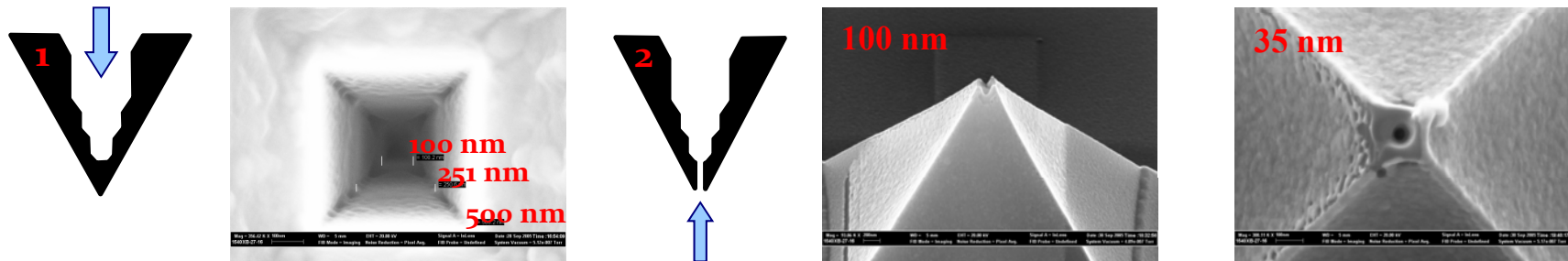
Meister et al, *Appl. Phys. Lett.* 2004
A.Fang, E. Dujardin, T.Ondarçuhu, *NanoLett* 2006

Tip fabrication

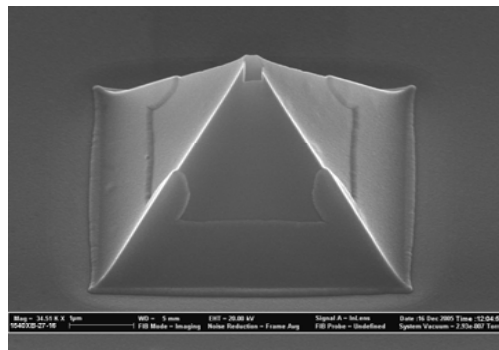
Channel milling by FIB

Standard AFM tip: pyramidal and gold coated

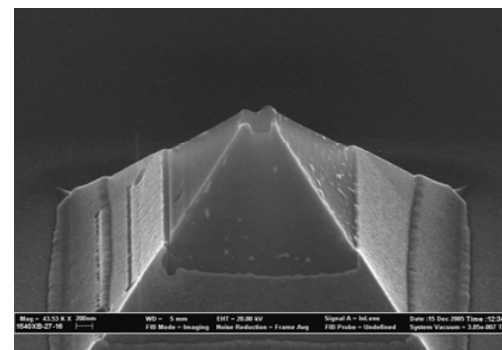
2 steps : (i) *thinning of the tip wall from the top* (ii) *milling at the tip apex from the tip side*
(record : 35 nm)



Surface functionalisation



Intact gold layer
(thiol chemistry)



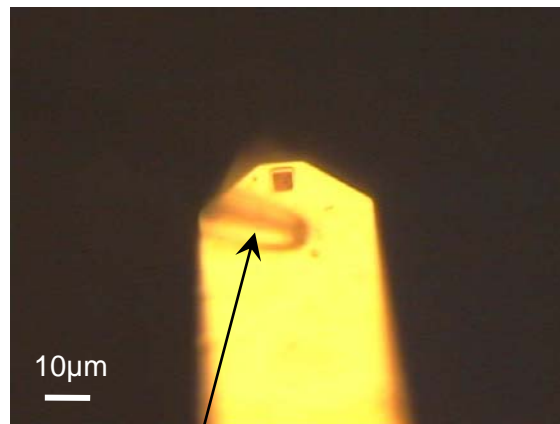
2 distinct areas : Si₃N₄ surface for silane
chemistry and gold layer for thiol treatment

Tip loading

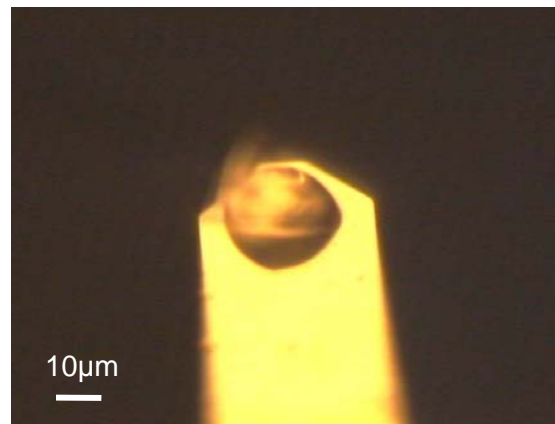
Deposited liquid

- Glycerol or glycerol-water mixture (dilution max 6:4)
- Solutions of molecules, proteins, nanoparticles...

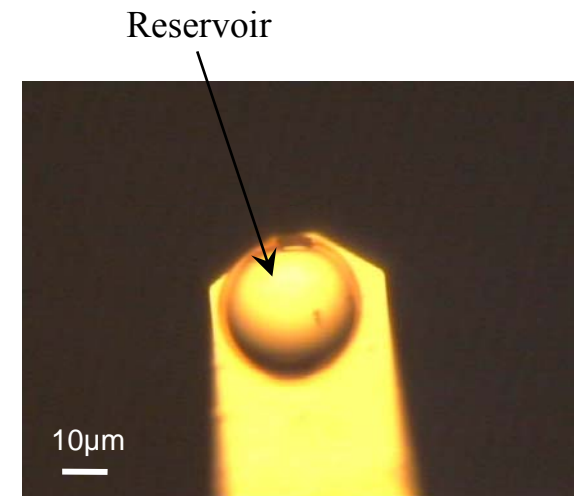
Loading of the reservoir



micropipette



Drop deposited with a micropipette
and a micromanipulator

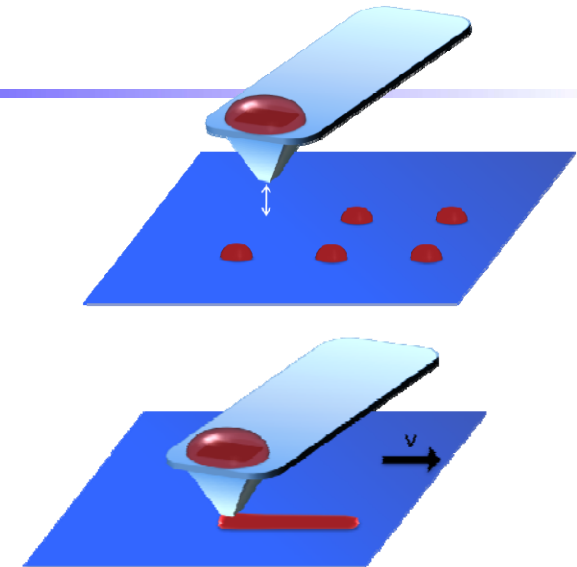


Deposition process

Deposition

Nanodroplet deposition : with an AFM in force spectroscopy mode

Line deposition : with an AFM in contact mode and using a nanopositioning table

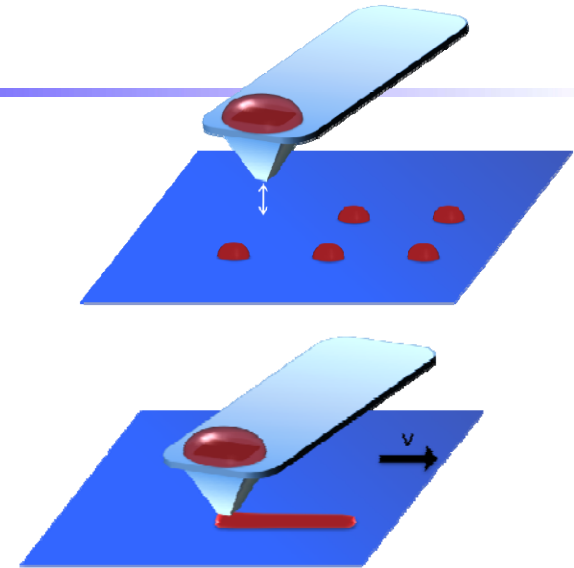


Deposition process

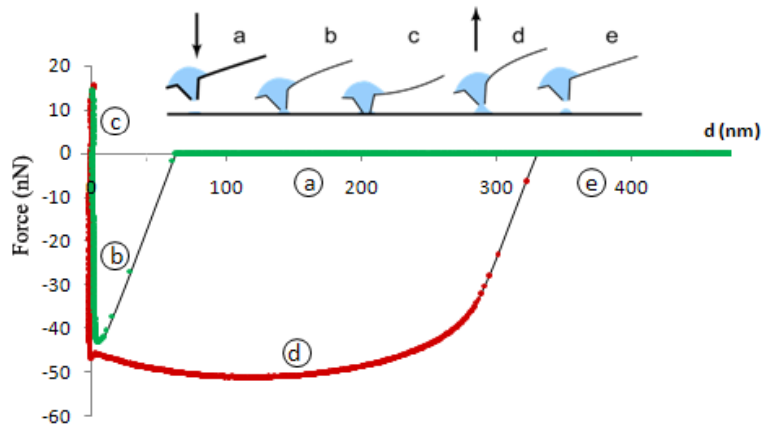
Deposition

Nanodroplet deposition : with an AFM in force spectroscopy mode

Line deposition : with an AFM in contact mode and using a nanopositioning table



Force curve recorded during liquid transfert

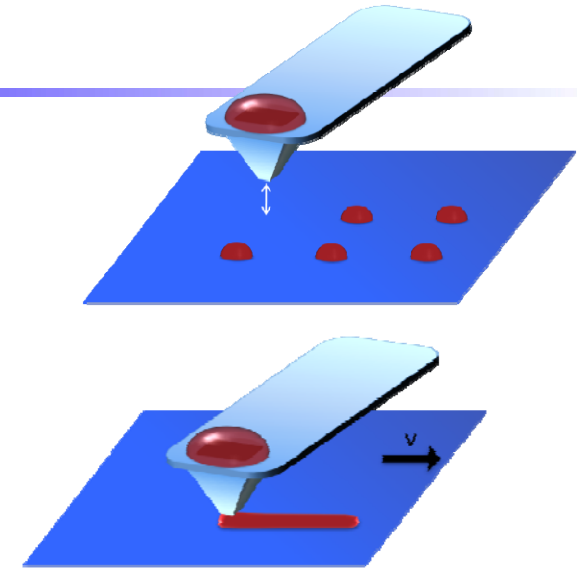


Deposition process

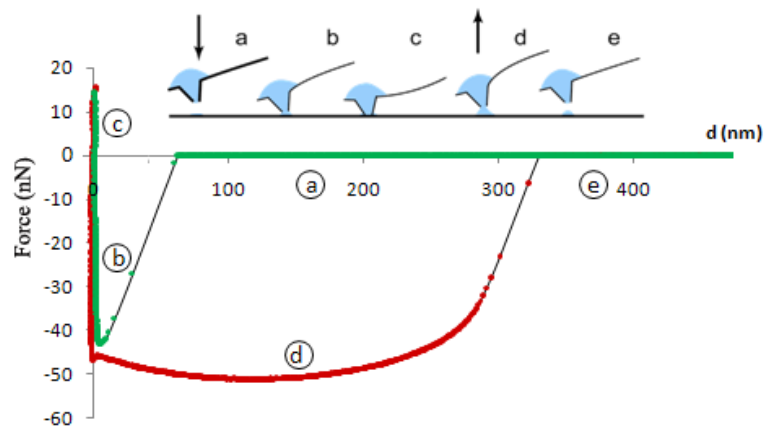
Deposition

Nanodroplet deposition : with an AFM in force spectroscopy mode

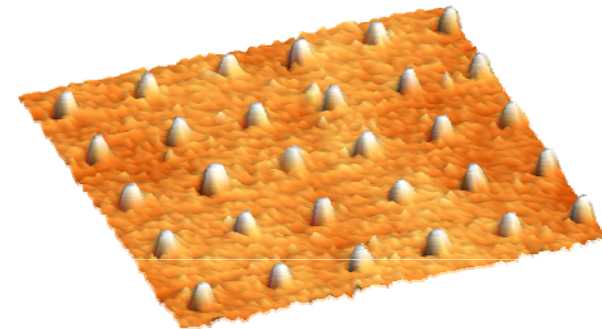
Line deposition : with an AFM in contact mode and using a nan positioning table



Force curve recorded during liquid transfert

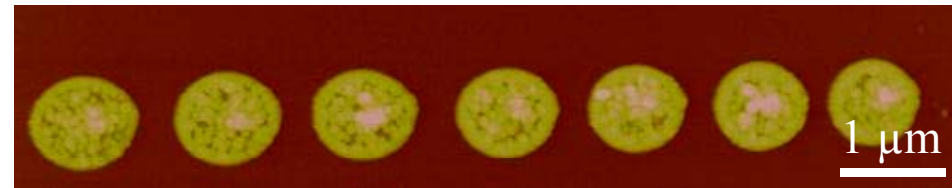
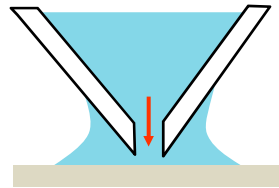


Deposit observation (after solvent evaporation)



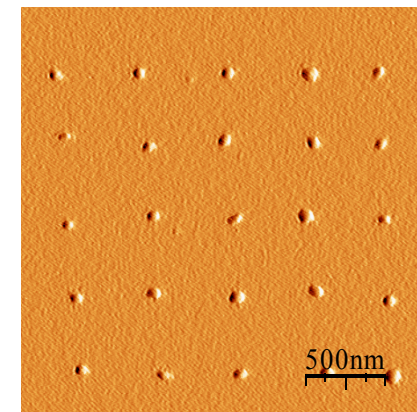
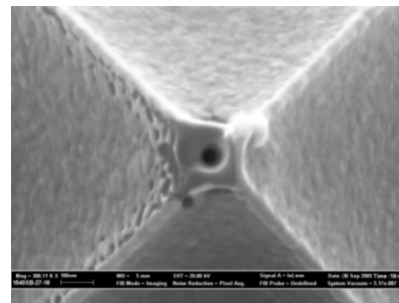
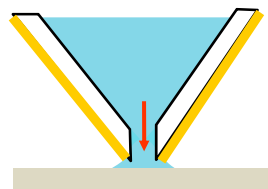
Nanodroplet deposition

Hydrophilic tip with an aperture of 400nm



Hydrophobic tip with an aperture of 35nm

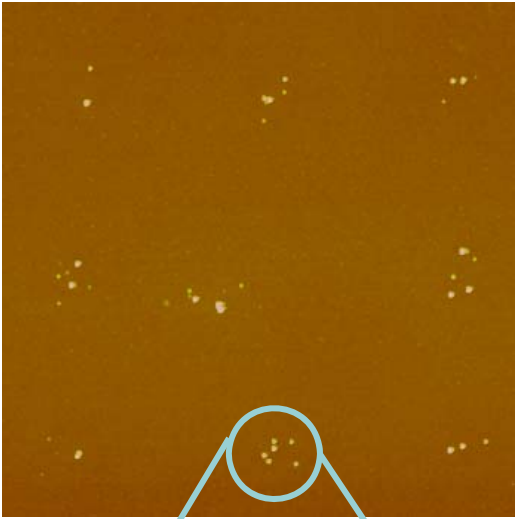
(treated with dodecanethiol)



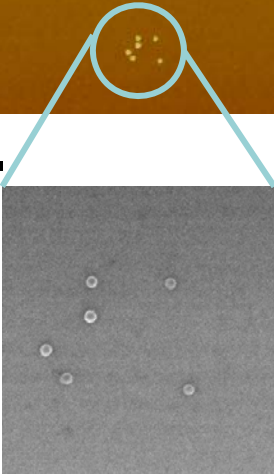
The influence of the different parameters is studied in : A. Fang, E. Dujardin, T.Ondarçuhu. *NanoLett* (2006)

Flexibility of the method

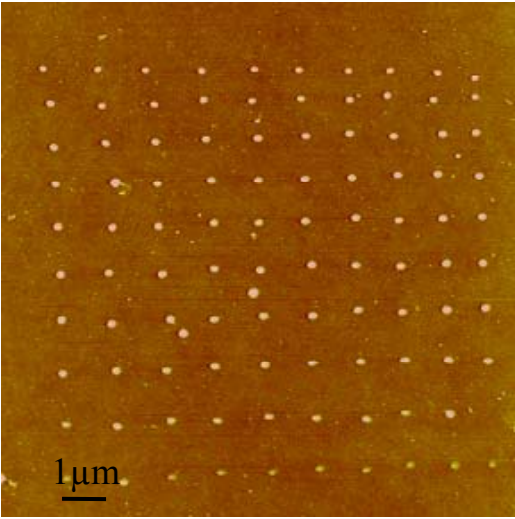
25 nm PS NPs



1 μm



DsRed Proteins

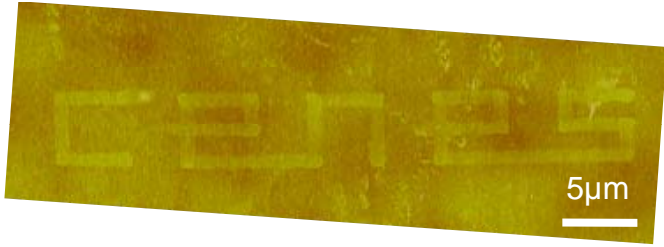


1 μm

Ruthenium complexes

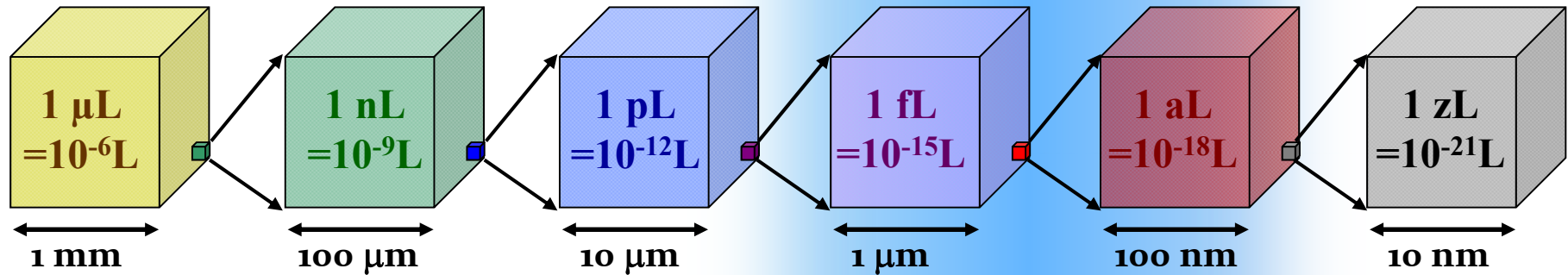
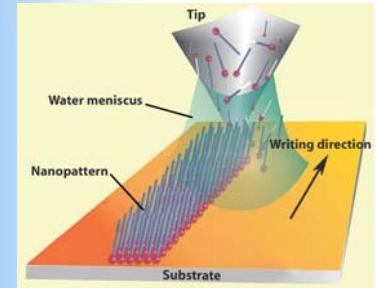
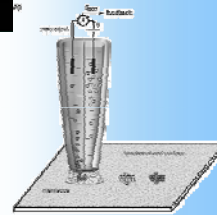
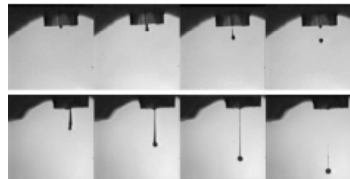
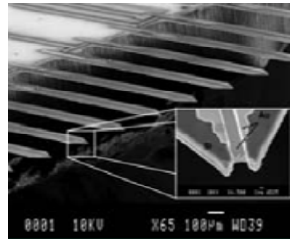
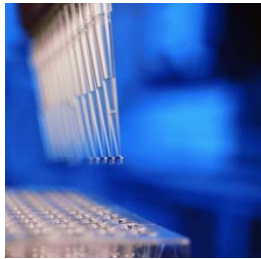


5 μm



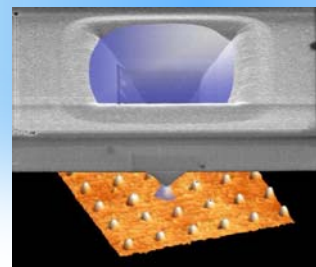
5 μm

Nanopatterning conclusion



LIQUID LITHOGRAPHY

NADIS

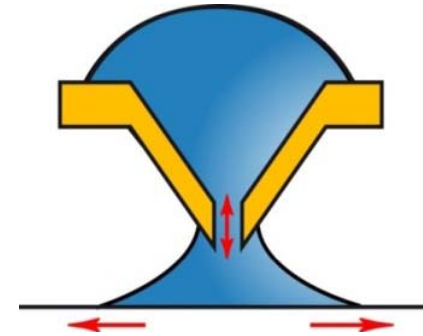


DIP PEN

Study of the deposition mechanisms

Final deposits due to :

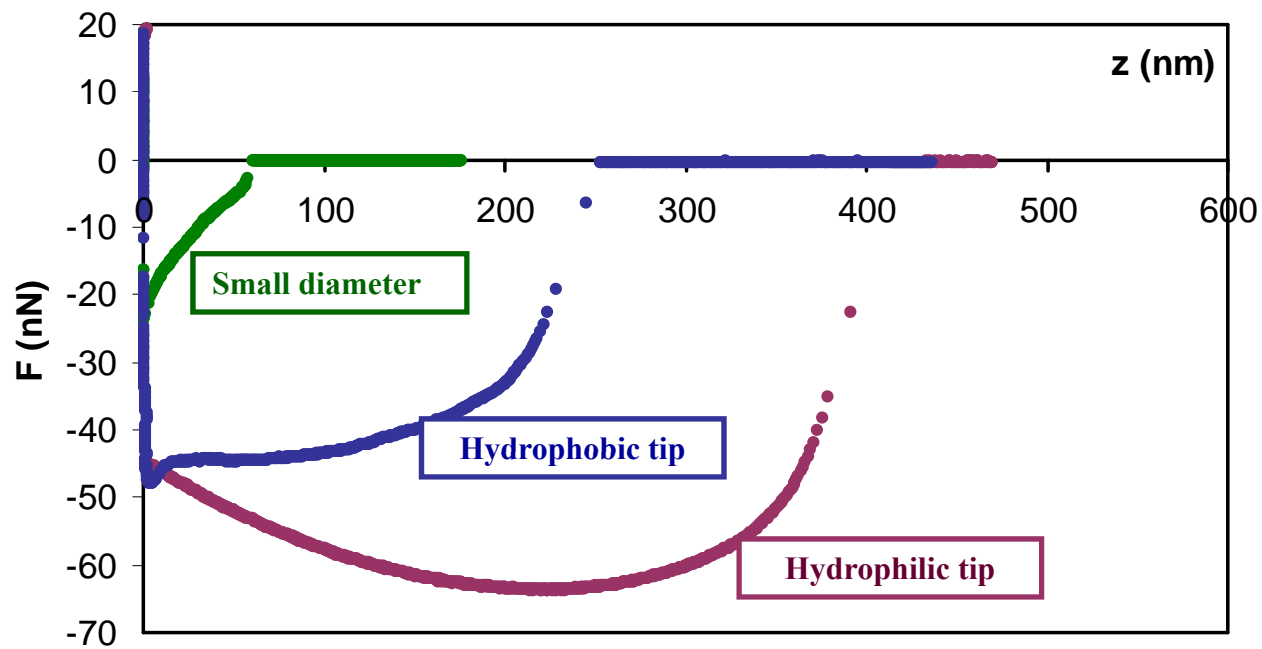
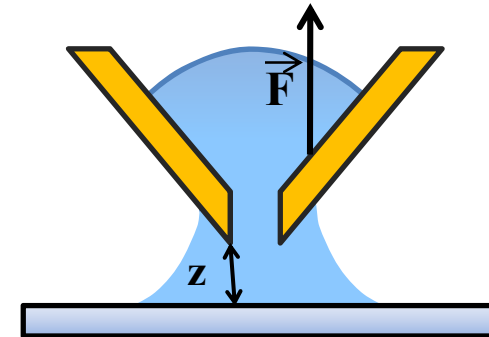
- flow through the channel
- spreading on the substrate surface



Analyse of the retraction force curves

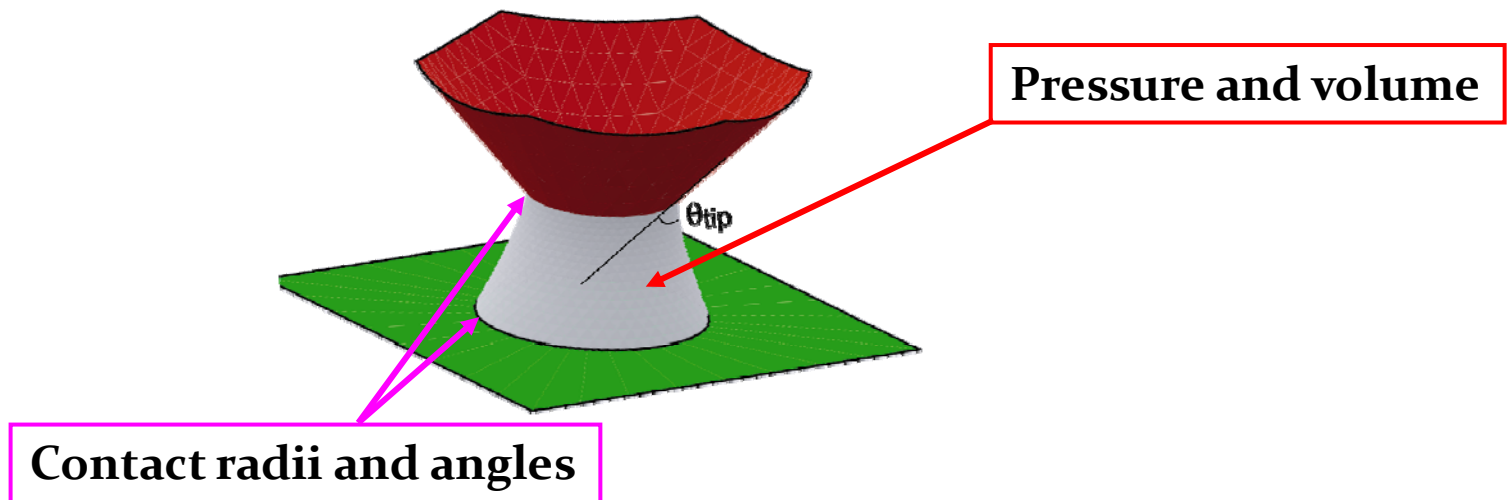
Force curve study :

- understanding the deposition mechanisms
- capillary force



Modeling with Surface Evolver

- Energy minimization for different **boundary conditions** and **constraints**



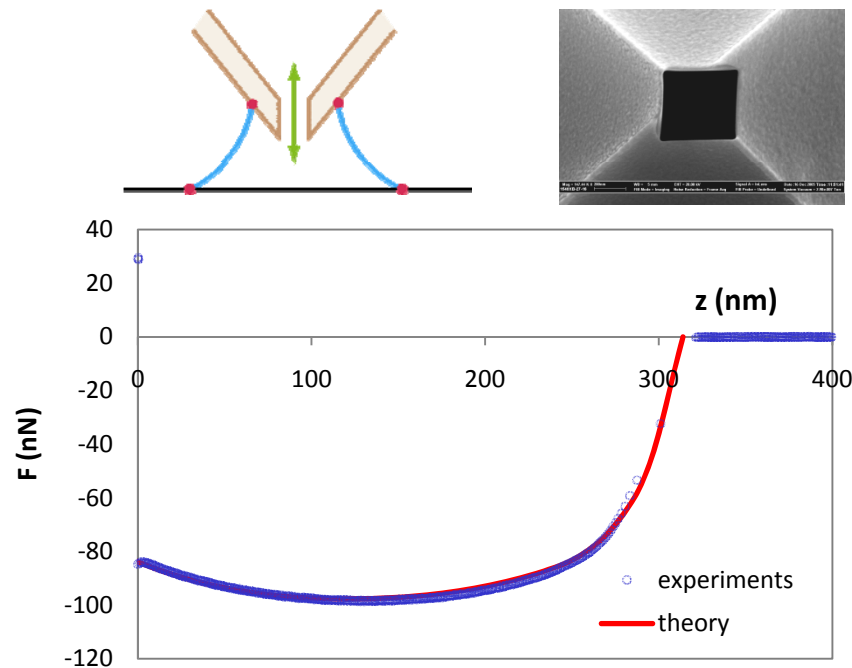
- surface shape
- Energy
- Pressure
- Volume
- Force

Hydrophilic NADIS tips

Boundary conditions : fixed radii on the tip and on the substrate

Channel of 280nm

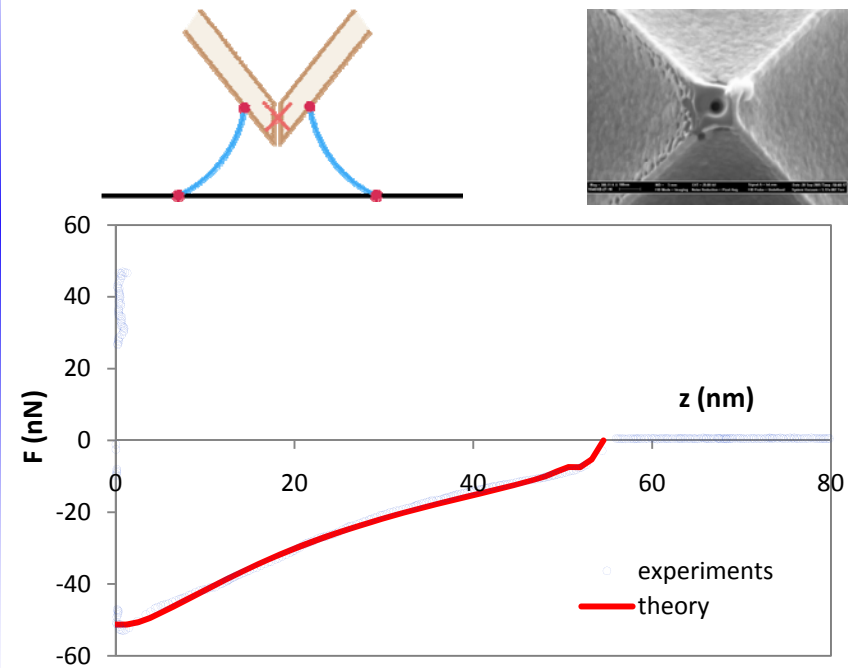
Constant pressure defined by the reservoir :
Laplace pressure of a spheric drop with a $20\mu\text{m}$ radius



$R_{\text{surf}} = 400$ nm, $R_{\text{tip}} = 250$ nm
 $P = 6.4 \cdot 10^3$ Pa

Channel of 35nm

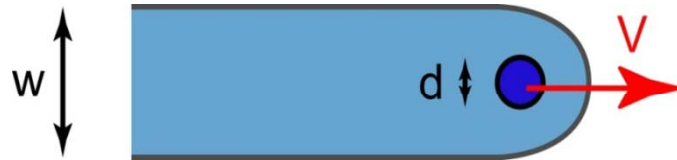
Constant volume : No liquid flow



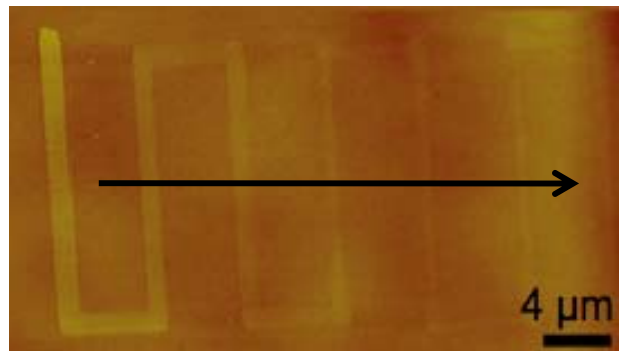
$R_{\text{surf}} = 97$ nm, $R_{\text{tip}} = 65$ nm
 $V = 0.4$ aL

More details on the influence of the different parameters on the force curve in :
L. Fabie, H. Durou, T. Ondarçuhu. *Langmuir* (2010)

Lines deposition



NADIS tip is moved at constant velocity while maintaining contact onto the surface thanks to a nanopositioning table incorporated to the AFM

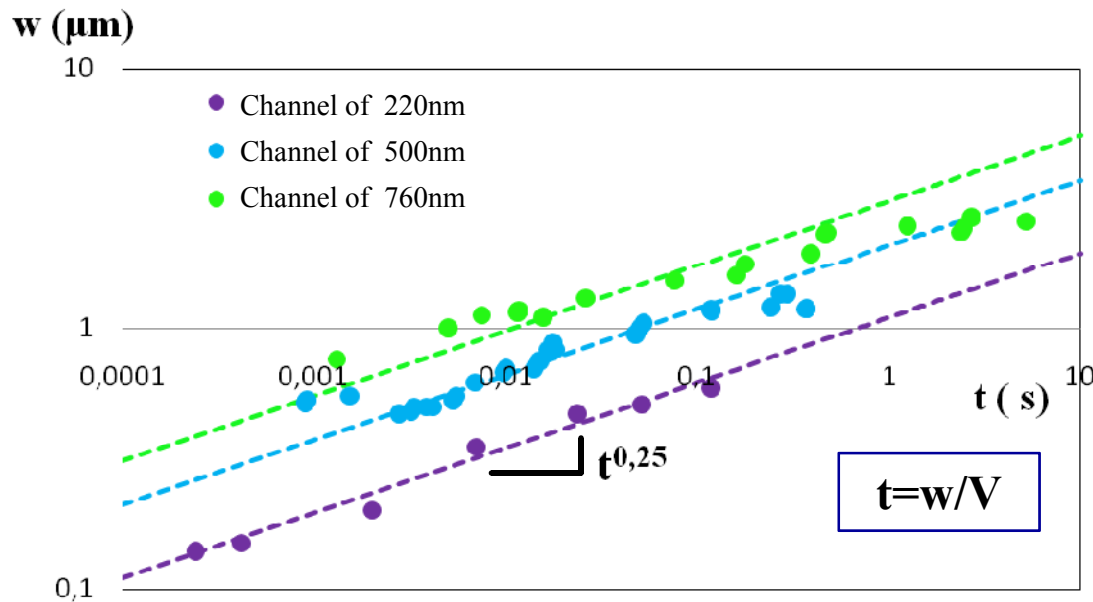
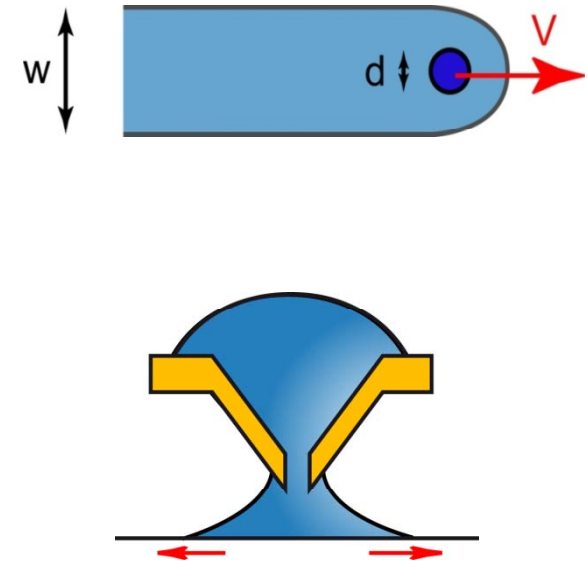
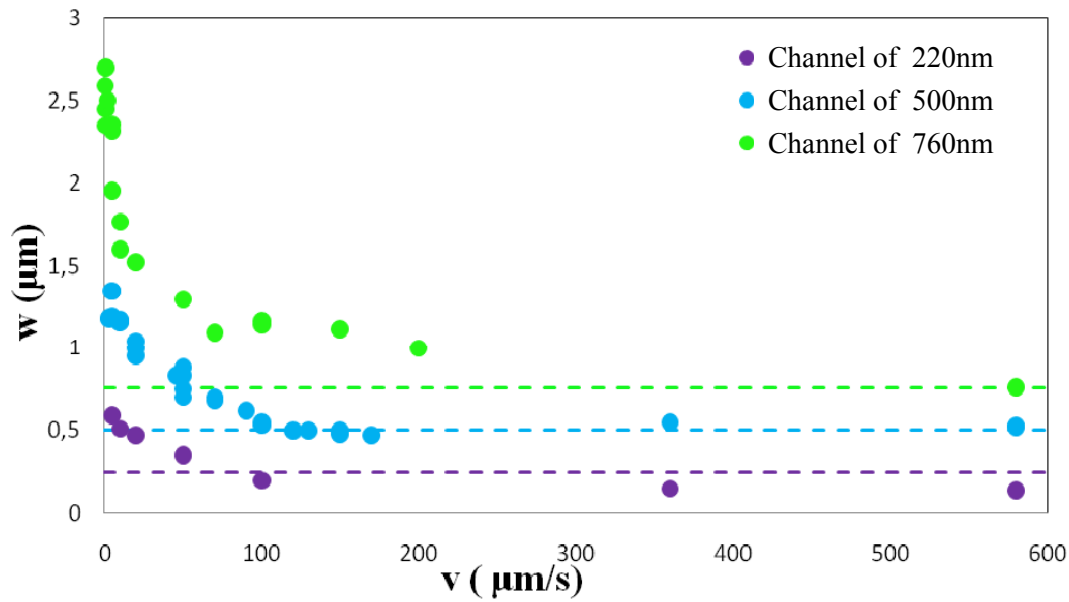


**Velocity
increasing**



Phase image for a
better contrast

Spreading dynamics



Different from diffusive law (Dip pen) in $t^{1/2}$

J. Jang et al. *J. Chem. Phys.* (2001)

Spreading dynamics

Cox-Voinov equation :

$$\theta^3 - \theta_m^3 = 9 \frac{\eta v}{\gamma} \ln \left(\frac{L}{l} \right)$$

O.V. Voinov, *Fluid Dyn.* (1976)
R.G. Cox, *J. Fluid. Mech.* (1986)

Classical case

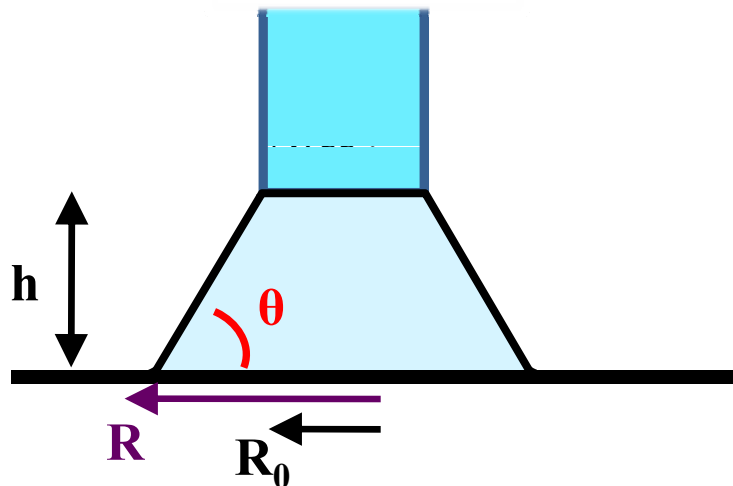


$$\theta \propto \frac{1}{R^3} \quad \text{Spreading at constant volume}$$

$$R \propto t^{1/10}$$

L. Tanner, *J. Phys. D* (1979)

NADIS case



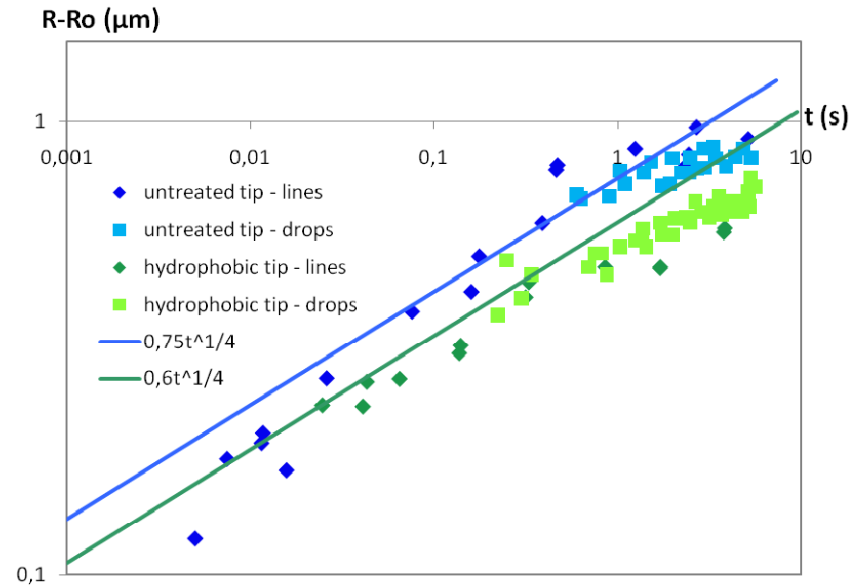
$$\tan \theta \approx \theta \approx \frac{h}{R - R_0} \quad \text{Spreading at constant pressure}$$

$$\left(\frac{h}{R - R_0} \right)^3 = \theta_m^3 + 9\alpha \frac{dR}{dt}$$

$$\alpha = \frac{\eta}{\gamma} \ln \left(\frac{L}{l} \right)$$

Results of the model

For $\theta_m = 0$, analytical solution :
 $R - R_0 = At^{1/4}$



For $\theta_m \neq 0$, numerical solution

$$\left(\frac{h}{R - R_0} \right)^3 = \theta_m^3 + 9\alpha \frac{dR}{dt}$$

$$\theta_m = 3.5^\circ$$

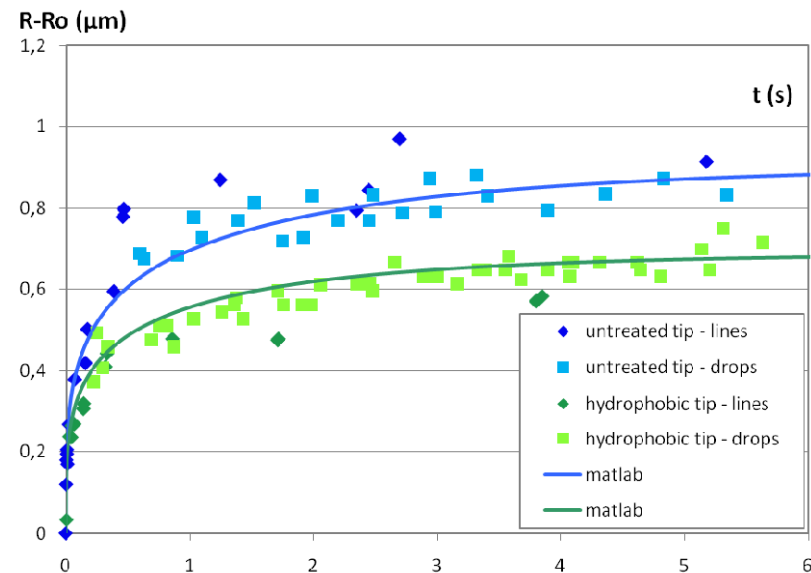
$$R_0 = 380 \text{ nm}$$

$$\ln(L/l) = 10$$

$$\alpha = 238 \text{ s/m}$$

untreated tip: $h = 56 \text{ nm}$

Hydrophobic tip : $h = 42.5 \text{ nm}$



Results of the model

For $\theta_m = 0$, analytical solution :
 $R - R_0 = At^{1/4}$

For $\theta_m \neq 0$, numerical solution

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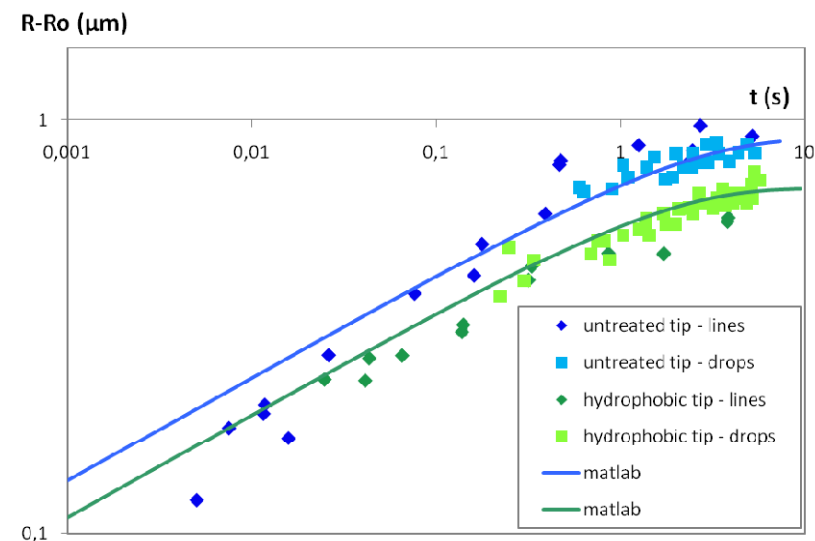
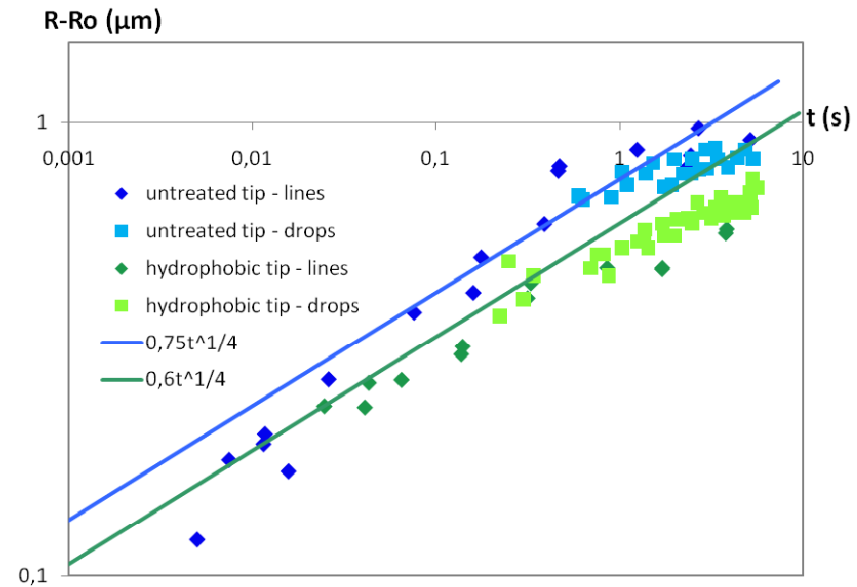
$$R_0 = 380 \text{ nm}$$

$$\ln(L/l) = 10$$

$$\alpha = 238 \text{ s/m}$$

untreated tip: $h = 56 \text{ nm}$

Hydrophobic tip : $h = 42.5 \text{ nm}$



Conclusion

Efficient method for nanopatterning

Fundamental studies

➤ *Study of the capillary force at the nanoscale*

useful for AFM imaging

➤ *Spreading dynamics at constant pressure*

interesting for printing techniques

